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## PATENT ABSTRACTS OF JAPAN

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(71)Applicant : FUJI DEBUISON KAGAKU KK

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(72)Inventor : ONO MICHIIHIRO

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(54) PREPARATION OF CLEAR EXTRACTION LIQUID OF TEA

(57)Abstract:

PURPOSE: To prepare extracted tea liquid preservable over a long period without causing browning and clouding and capable of keeping the taste and flavor of the liquid, by contacting an extracted tea liquid with a specific silica gel.

CONSTITUTION: An extracted tea liquid is made to contact with 0.01W5w/v% silica gel selected from a silica hydrogel, silica xerogel or a silica gel having intermediate properties between silica hydrogel and silica xerogel and having a specific surface area of 100W1,000m<sup>2</sup>/g (by BET process), a pore volume of 0.3W2.0ml/g, an average pore diameter of 10W500Å; and a water-content of ≤70% (wet basis) and the silica gel is separated from the mixture. As an alternative method, an extracted tea liquid is passed through a column packed with the above silica gel.

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